

Power Discretes

About this document

Scope and purpose

This document is intended to provide additional information on radiation testing performed by International Rectifier HiRel (IR HiRel) and answer the frequently asked questions.

Intended audience

This document is intended for design engineers, application engineers, and system engineers to understand IR HiRel discretes qualified for use in space applications.

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Rad hard devices

1 Rad hard devices

1.1 What is rad hard?

Radiation hardened (rad hard) refers to the process by which the devices are made to be resistant against effects of radiation that otherwise would result in destructive or non-destructive damage.

1.2 How rugged are your devices against single-event effects and degradation due to total ionizing dose?

IR HiRel's MOSFETs are tested for SEE with heavy ions having LET of 37-92 MeV·mg/cm². The beam energy can be in range of 300 MeV – 2.2 GeV. These devices are designed to withstand total ionizing dose from 100 krad to 1 Mrad without damage.

1.3 How has the radiation testing changed or improved over the past years?

For the older generation devices (e.g. R4), SEE testing using heavy ions was performed at Brookhaven National Laboratory (BNL)'s Tandem Van De Graff facility. During radiation testing, IR HiRel's goal is to test devices such that heavy ions initiate an SEE event and so that a safe operating area can be accurately established. Initially the beam energy available was limited (up to 500 MeV) however a higher energy beam became available at the Cyclotron Institute of Texas A&M University (TAMU). The newer devices are tested with beam energy of upto 2.2 GeV at this facility and allows to have the range at Bragg's peak to be near the sensitive area of the device under test (DUT).

2 Radiation testing

2.1 What is the flux and fluence level?

The flux and fluence* ranges in the order of 10⁴ ions/cm²/sec and 10⁵ ions/cm² respectively.

2.2 What is Bragg's peak?

When a charged particle hits the device, as it traverses through the material of device, it loses its energy through ionization. This distance is called Bragg Depth. Energy of the charged particle is at its maximum before stopping and subsequently reduces to zero. The distance at which the stopping power is maximum is called Bragg Peak.

2.3 Why are degraders used?

The purpose of degrader is to manipulate beam energy so that range at Bragg peak is close to the sensitive region of DUT. Degrader can be moved at different angles or have different thickness which will change the beam energy.

2.4 What is the reason behind selection of ions?

As the ion traverses through the device it deposits energy and travel to certain distance inside the DUT. IR HiRel typically selects Krypton, Xenon and Gold ions with LETs of approximately 37, 60 and 90 MeV·mg/cm² respectively which can potentially induce an SEE event.

2.5 What is range? Why does it say "range in Si"?

Range (as mentioned in the datasheet) is the distance that the heavy ion traverses inside the DUT. Silicon (Si) is primarily used as a reference material since semiconductor devices are built on silicon.

2.6 What's the relation between ion size, energy, range and LET?

With a beam of particular MeV/u, larger ions having higher atomic number also have higher energy. The LET at Bragg's peak is the highest. (For example, See Figure 2)

2.7 Why is angle of incidence equal to zero?

Si MOSFETs are a vertical device and the worst-case for radiation testing is when the beam is at a normal to the DUT.

^{*} Flux: The number of ions passing through a one cm² area perpendicular to the ion beam per unit of time, expressed as ions/cm²•s Fluence: The ion flux integrated over the time required for the run, expressed as ions/cm².



Radiation testing

2.8 Based on what criteria do you qualify the devices (i.e. pass or fail)?

Si MOSFETs are tested for SEE performance based on MIL-PRF-19500, TM 1080. During irradiation I_{DSS} , I_{GSSf} and I_{GSSr} are measured whose limits are predetermined. The device fails if it passes these threshold limits. Post-irradiation, the device is tested for gate-integrity in PIGS test. It requires two failures for characterization and three passes for qualification.

2.9 What's the difference between standard and worst-case beam conditions?

The heavy ion beam available at Tandem Van De Graff Facility, BNL has kinetic energies that are lower compared to the beam available at Cyclotron Institute, TAMU so the range at Bragg peak (inside the device) is lesser. These are called standard beam conditions.

Worst case beam conditions refer to the testing conditions when the heavy ions are penetrating deeper into the device structure. This becomes possible when the same ions have higher kinetic energy and have larger range at Bragg peak. In other words, ion beam settings which place the Bragg peak at the bottom epi/substrate interface has been proposed as "worst case." This interface is often called as critical area or the most sensitive region for SEE. Such beam conditions are available at TAMU.

2.10 What's the difference between radiation testing performed at BNL versus TAMU?

BNL uses Tandem Van De Graff accelerator to deliver heavy ion beams with kinetic energy of upto 5 MeV/nucleon (for high atomic number) and the testing is available only in vacuum.

TAMU has superconducting cyclotron at Cyclotron Institute with heavy ion beam energy of 10, 25 and 40 MeV/nucleon. The testing is available in both, vacuum and air.

2.11 Why do you perform radiation test on bare die?

Different test samples can have different packages and using a delidded device removes that variable. The package does not degrade the radiation performance of device.

2.12 What is PIGS test?

PIGS stands for Post Irradiation Gate Stress. After each irradiation run, a gate-stress test is performed to verify device functionality.

2.13 What's the purpose of Al degrader and degrader angle?

The beam energy is reduced by means of a *degrader* system with foils having a suitable thickness and *orientation* with respect to the incident beam. Each foil can be inserted, withdrawn, and rotated remotely through use of computer controls.



Radiation testing

2.14 What is "Clean and Baked"?

If there's an "unexpected" failure, or a failure that doesn't match other samples, we may perform a clean and bake to confirm that the part wasn't somehow contaminated and is presenting a false failure.

An SEE failure will not recover. So, if we are able to perform a clean and bake and the part recovers, it means that the failure was not related to the SEE test. As SEE samples have no lids, there is a danger that handling (such as loading and unloading onto boards) can expose the part to this potential false failure mode.



Appendix A - SEE beam data

Texas A&M University:

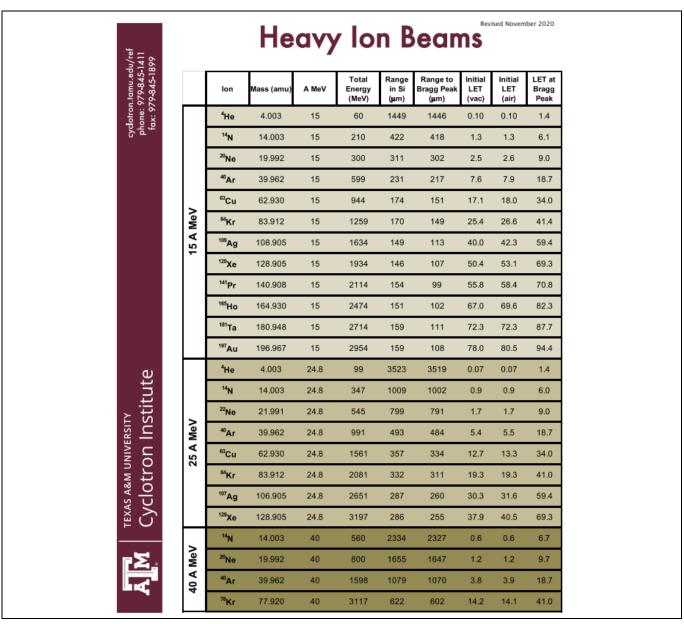


Figure 1 Heavy Ions Beam List - Ion Species, LET, Range to Bragg Peak

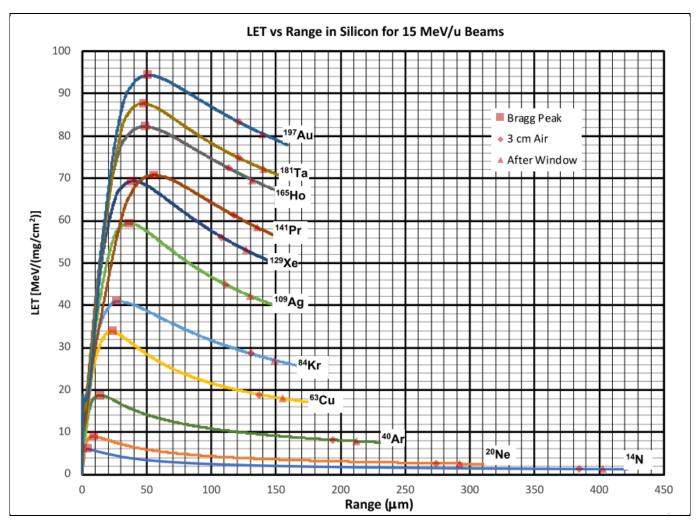


Figure 2 LET v/s Range in Si for different ions (Image Courtesy: Texas A&M University)

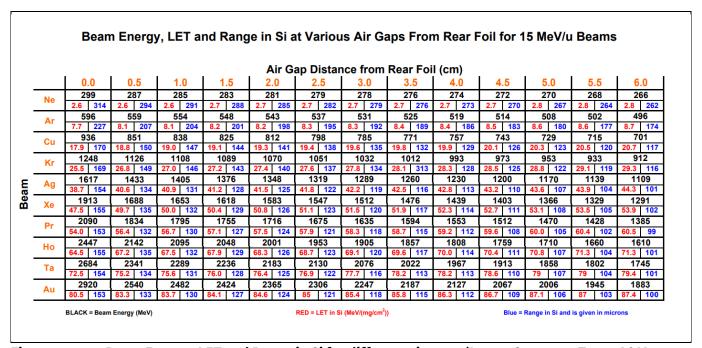


Figure 3 Beam Energy, LET and Range in Si for different air-gaps (Image Courtesy: Texas A&M University)



Brookhaven National Laboratory

			e range of 1 particle/cm²/sec n 1 · 10 ⁶ particles/cm²/sec.			In Silicon	
			Mass	Max Energy		Surface LET	Range
	Z	Symbol	AMU	MeV	MeV/AMU	MeV/mg/cm ²	Microns
	1	¹ H	1.0079	28.75	28.52	0.0153	4550
	3	⁷ Li	7.016	57.2	8.15	0.369	390
	5	¹¹ B	11.0093	85.5	7.77	1.08	206.13
	6	¹² C	12	99.6	8.3	1.46	180.43
	8	¹⁶ O	15.9994	128	8	2.61	137.78
	9	¹⁹ F	18.9954	142	7.48	3.51	118.88
1	12	²⁴ Mg	23.9927	161	6.71	6.01	84.16
1	14	²⁸ Si	28.0855	187	6.66	7.81	77.16
	17	³⁵ CI	34.9688	212	6.06	11.5	64.41
2	20	⁴⁰ Ca	39.9753	221	5.53	15.8	51.89
2	22	⁴⁸ Ti	47.9479	232	4.84	19.6	47.8
2	24	⁵² Cr	51.9405	245	4.72	22.3	45.86
2	26	⁵⁶ Fe	55.9349	259	4.63	25.1	44.24
2	28	⁵⁸ Ni	57.9353	270	4.66	27.9	44.56
2	29	⁶³ Cu	62.9296	277	4.4	30.1	42.06
3	32	⁷² Ge	71.9221	273	3.8	35.9	37.94
3	35	⁸¹ Br	80.9163	287	3.55	41.3	37.5
	41	⁹³ Nb	92.906	300	3.23	47.5	36.32
	47	¹⁰⁷ Ag	106.9051	313	2.93	59.2	32.48
Ę	53	¹²⁷	126.9045	322	2.54	66.9	32.54
7	79	¹⁹⁷ A u	196.9665	337	1.71	84.6	29.21

Figure 4 Heavy Ions Beam List (Credits: BNL)

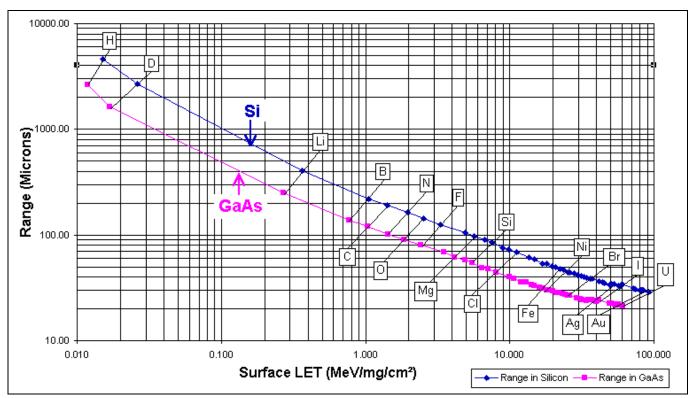


Figure 5 Range v/s Surface LET in Si for different ions (Credits: BNL)



Radiation testing

Revision history

Document version	Date of release	Description of changes
1.0	2021-11-08	Initial release

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